

4/3/03

Substitute for form 1449A/PTO		Complete If Known	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>		Application Number	101631283
		Filing Date	Concurrently Herewith
		First Named Inventor	Cesar M. Garza et al.
		Group Art Unit	1936
		Examiner Name	Barra
(use as many sheets as necessary)		Attorney Docket Number	SC12879TP
Sheet		of	

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number Number-Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
nm	AA	6,245,489 B1	06/12/2001	Baklanov et al.	430/43
nm	AB	US2003/0118935 A1	06/26/2003	Matsuzawa	430/270.1

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document Country Code <sup>3</sup> Number <sup>4</sup> Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>

NON PATENT LITERATURE DOCUMENTS			
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nm	AC	Kudo et al., "CD Changes of 193nm Resist During SEM Measurement," <i>Advances in Resist Technology and Processing XVIII</i> , Francis M. Houlihan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4345, pp. 179-189.	
nm	AD	Vasconi et al., "193nm Metrology: facing severe e-beam/resist interaction phenomena," <i>Metrology, Inspection, and Process Control for Microlithography XV</i> , Neal T. Sullivan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4344, pp. 653-661.	
nm	AE	Wu et al., "Investigation on the Mechanism of the 193nm Resist Linewidth Reduction During the SEM Measurement," <i>Advances in Resist Technology and Processing XVIII</i> , Francis M. Houlihan, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4345, pp. 190-199.	

Examiner Signature		Date Considered	8/24/05
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